

ABSTRACT

Disclosed is a furnace tube apparatus related to the technical field of semiconductor equipment, comprising an inner tube, an outer tube, a first evacuation port, and a second evacuation port, a process space is formed inside the inner tube, the outer tube is sleeved outside the inner tube, a gap region is present between the outer tube and the inner tube, and the inner tube is provided with an exhaust port to connect the process space and the gap region. The first evacuation port is in communication with the process space, and the second evacuation port is in communication with the gap region. In the present invention, the first evacuation port is in direct communication with the process space, and the second evacuation port is in direct communication with the gap region. Compared with the single evacuation port design, the gas in the process space can be directly evacuated through the first evacuation port, and the gas in the gap region between the inner tube and the outer tube can be directly evacuated through the second evacuation port. During the process, gas can be evacuated more quickly, thereby improving the production efficiency of the furnace tube apparatus.